



UNITED STATES PATENT and TRADEMARK OFFICE

UNDER SECRETARY OF COMMERCE FOR INTELLECTUAL PROPERTY AND  
DIRECTOR OF THE UNITED STATES PATENT AND TRADEMARK OFFICE  
WASHINGTON, D.C. 20231  
WWW.USPTO.GOV

DEC - 2 2001

In re Application of:  
Hoiman (Raymond) Hung  
Serial No. 09/276,376  
Filed: March 25, 1999  
For: ENHANCEMENT OF SILICON  
OXIDE ETCH RATE AND NITRIDE  
SELECTIVITY USING HEXAFLUORO-  
BUTADIENE OR OTHER HEAVY PER-  
FLUOROCARBON

NOTICE OF WITHDRAWAL  
FROM ISSUE UNDER  
37 CFR 1.313 (b)

RECEIVED  
DEC 9 2002  
TC 1700

The above-identified application is withdrawn from issue after payment of the issue fee due to: reopening of prosecution. See 37 CFR 1.31(b).

The above-identified application is hereby withdrawn from issue.

The issue fee is refundable upon written request. If, however, the application is again found allowable, the issue fee can be applied toward payment of the issue fee in the amount identified on the new Notice of Allowance and Issue Fee Due upon request. This request and any balance due must be received on or before the due date noted in the new Notice of Allowance in order to prevent abandonment of the application.

Telephone inquiries should be directed to Randy Gulakowski at (703) 308-4333.

The above-identified application is being forwarded to the examiner for prompt appropriate action, including applicant of the new status of this application.

*Jacqueline M. Stone*

Jacqueline M. Stone, Director  
Technology Center 1700  
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09/276,376

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cc: Allowed Files-PK3-910